

<b>Notice of References Cited</b>	Application/Control No. 10/692,243		Applicant(s)/Patent Under Reexamination SHERMAN, ARTHUR	
	Examiner Eric B. Fuller		Art Unit 1762	Page 1 of 1

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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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